OIPE JC106 AUG 23 2004 PATENT & TRADEMARK OFFICE

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

NAKAMURA, Tsuyoshi, et al.

Docket No: Q78034

Appln. No.: 10/685,432

Group Art Unit: 1752

Confirmation No.: 5728

Examiner: Yvette C. Thornton

Filed: October 16, 2003

For: NOVEL COPOLYMER, PHOTORESIST COMPOSITION, AND PROCESS FOR FORMING RESIST PATTERN WITH HIGH ASPECT RATIO

AMENDMENT UNDER 37 C.F.R. § 1.111

MAIL STOP AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated May 21, 2004, being filed on August 23, 2004 as August 21, 2004 fell on the previous Saturday, please amend the above-identified application as follows on the accompanying pages.

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